EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S6	544	((semiconductor or substrate or wafer) near5 (wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat$4 or rins$4 or etch$4) near5 (acid or etchant or water or liquid or solution)) AND ((wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat$4 or rins$4 or etch$4) NEAR5 (COMPARTMENT OR CHAMBER OR CONTAINER OR RECEPTACLE OR VESSEL OR TUB OR VAT OR TANK OR BATH OR BOWL)) AND ((DRY$4 OR DRYER) NEAR5 (COMPARTMENT OR CHAMBER OR ENCLOSURE OR COVER OR COVERING SHELL OR HOOD)) AND ((semiconductor or substrate or wafer) near5 (RAIS$4 OR LIFT$4 OR ELEVAT$4 OR UPWARD$4)) AND ((semiconductor or substrate or wafer) near5 (LOWER$4 OR DIP$4 OR DOWN)) AND ((DRY$4 OR DRYER OR ENCLOSURE OR COVER OR COVERING SHELL OR HOOD OR VAPOUR OR GAS OR VAPOR OR FUMES) NEAR5 (EXHAUST$4 OR PURG$4 OR VENT$4 IR VENTILAT$4 OR VACUUM$4 OR "LOW PRESSURE" OR EVACUAT$4 OR WITHDRAWN))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/19 18:18

| S15 | 185 | ((semiconductor or substrate or wafer) near5 (wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat$4 or rins$4 or etch$4)) AND ((wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat$4 or rins$4 or etch$4) NEAR5 (COMPARTMENT OR CHAMBER OR CONTAINER OR RECEPTACLE OR VESSEL OR TUB OR VAT OR TANK OR BATH OR BOWL)) and ((IPA or alcohol) near5 (GASEOUS OR gas or vapor$4 OR VAPOUR$4) near5 (supply or source or spray$4 or nozzle or manifold or jet$4 or inlet)) AND ((DRY$4 OR DRYER OR DRIER OR DRIED) NEAR5 (NITROGEN OR COMPARTMENT OR CHAMBER OR ENCLOSURE OR COVER OR COVERING SHELL OR HOOD)) AND ((semiconductor or substrate or wafer) near5 (RAIS$4 OR LIFT$4 OR ELEVAT$4 OR UP UPWARD$4)) AND ((semiconductor or substrate or wafer) near5 (LOWER$4 OR DIP$4 OR DOWN$4 OR IMMERS$4 OR SUBMERG$4 OR SUBMERS$4)) AND ((DRY$4 OR DRYER OR DRIER OR ENCLOSURE OR COVER OR COVERING SHELL OR HOOD OR VAPOUR OR GAS OR GASEOUS OR VAPOR OR FUMES) NEAR5 (EXHAUST$4 OR PURG$4 OR VENT$4 OR VENTILAT$4 OR VACUUM$4 OR "LOW PRESSURE" OR EVACUAT$4 OR WITHDRAWN OR SUCTION$4 OR SUCK$4)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/12/20 10:12 |

| S32 | 380 | ((semiconductor or substrate or wafer) near5 (DRY$4 OR DRYER OR DRIER OR DRIED OR wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat$4 or rins$4 or etch$4)) AND ((DRY$4 OR DRYER OR DRIER OR DRIED OR wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat$4 or rins$4 or etch$4) NEAR5 (LIQUID OR ACID OR WATER OR ETCHANT OR ALCOHOL OR IPA)) AND ((VAPOUR OR GAS OR GASEOUS OR VAPOR OR FUMES) NEAR5 (EXHAUST$4 OR PURG$4 OR VENT$4 OR VENTILAT$4 OR VACUUM$4 OR "LOW PRESSURE" OR EVACUAT$4 OR WITHDRAWN OR SUCTION$4 OR SUCK$4 OR ASPIRAT$4 OR EDUCT$4) NEAR5 (SECONDARY OR AUXILIARY OR EXTRA OR BACKUP OR ASSIST$4 OR COMPLEMENTARY)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/12/20 11:58 |
| S42 | 236 | ((semiconductor or substrate or wafer) near5 (DRY$4 OR DRYER OR DRIER OR DRIED OR wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat$4 or rins$4 or etch$4) NEAR5 (COMPARTMENT OR CHAMBER OR ENCLOSURE OR COVER OR COVERING SHELL OR HOOD OR CONTAINER OR RECEPTACLE OR VESSEL OR TUB OR VAT OR TANK OR BATH OR BOWL)) AND ((DRY$4 OR DRYER OR DRIER OR DRIED OR wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat$4 or rins$4 or etch$4) NEAR5 (LIQUID OR ACID OR WATER OR ETCHANT OR ALCOHOL OR | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/12/20 15:43 |

		IPA)) AND ((VAPOUR OR GAS OR GASEOUS OR VAPOR OR FUMES) NEAR3 (EXHAUST$4 OR PURG$4 OR VENT$4 OR VENTILAT$4 OR VACUUM$4 OR "LOW PRESSURE" OR EVACUAT$4 OR WITHDRAWN OR SUCTION$4 OR SUCK$4 OR ASPIRAT$4 OR EDUCT$4) NEAR3 (SECOND$4 OR ANCILLIARY OR AUXILIARY OR EXTRA OR BACKUP OR ASSIST$4 OR COMPLEMENTARY)) AND ((VAPOUR OR GAS OR GASEOUS OR VAPOR OR FUMES) NEAR3 (EXHAUST$4 OR PURG$4 OR VENT$4 OR VENTILAT$4 OR VACUUM$4 OR "LOW PRESSURE" OR EVACUAT$4 OR WITHDRAWN OR SUCTION $4 OR SUCK$4 OR ASPIRAT $4 OR EDUCT$4) NEAR3 (COMPARTMENT OR CHAMBER OR ENCLOSURE OR COVER OR COVERING SHELL OR HOOD OR CONTAINER OR RECEPTACLE OR VESSEL OR TUB OR VAT OR TANK OR BATH OR BOWL))					
S70	431	134/104.2.CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/20 20:13
S72	598	134/902.CCLS.	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/12/20 20:14
S73	1769	134/902.CCLS.	USPAT	OR	ON	2009/12/20 20:14
S74	375	134/902.CCLS.	US-PGPUB	OR	ON	2009/12/20 20:14

12/21/09 11:59:46 AM
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